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Intel Silicon Technologies								
	Aı	new p	proce	ess ev	ery 2	years	S	
	Process Name	<u>P856</u>	<u>P858</u>	<u>Px60</u>	<u>P1262</u>	<u>P1264</u>	<u>P1266</u>	<u>P1268</u>
	1st Production	1997	1999	2001	2003	2005	2007	2009
	Lithography	.25µm	.18µm	.13µm	90nm	65nm	45nm	32nm
	Gate Length	.20µm	.13µm	<70nm	<50nm	<35nm	<25nm	<18nm
	Wafer Size (mm)	200	200	200/300	300	300	300	300
•		Production Developm				velopmen	nt	Research
	All dates spe	cified are targe	t dates provide	ed for planning pu	irposes only ar	nd are subject to	o change.	
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